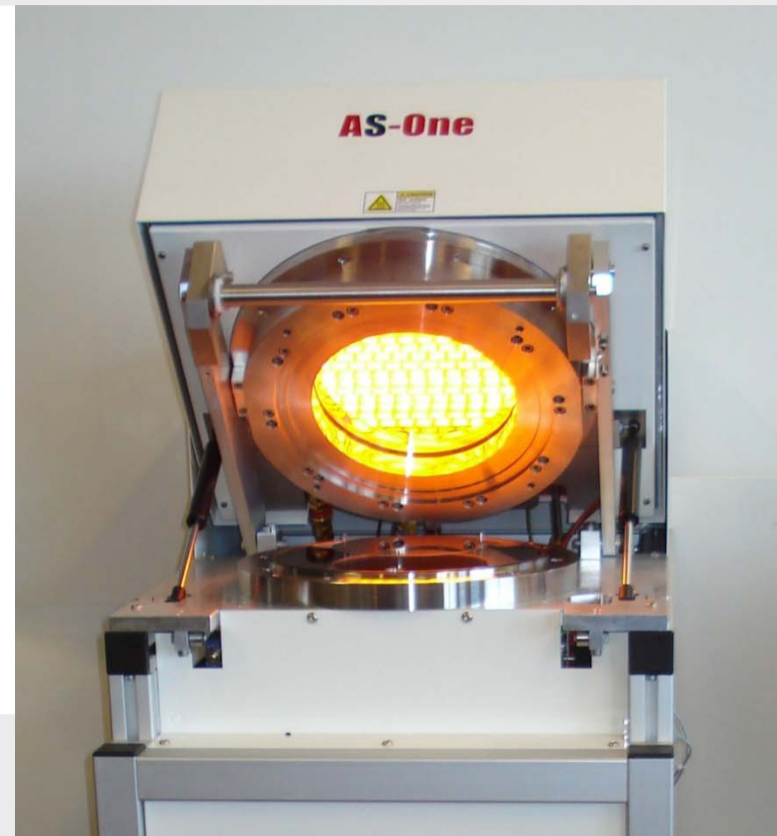


# AS-ONE

## Rapid Thermal Processing

- InGaN annealing
- Contact alloying
- Sapphire , GaAs, InP
- 4" and 6" capability



## ANNEALSYS

Extended pyrometer control range: 150 C to 1250 C  
Fast digital PID temperature controller

Edge pyrometer for enhanced temperature control of compound semiconductors and sapphire substrates processing with susceptor.

## SPECIFICATIONS

**Stainless steel cold wall chamber technology:**

- High cooling rates and low memory effect
- High process reproducibility
- Ultra clean and contamination-free environment

**Extended temperature range:**

- Room temperature up to 1250 C

Floor standing system for reduced footprint  
High reliability and low cost of ownership

High vacuum version ( $10^{-6}$  mbar) is available

